

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria. Virginia 22313-1450 www.uspto.gov

APPLICATION N	0.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/706,244	1,	11/12/2003	Ravi lyer	Ravi Iyer 3965.4US (94-0194.04/US) 6407 EXAMINER	
24247	7590	07/21/2004			
TRASK BRITT				EVERHART, CARIDAD	
P.O. BOX 2550 SALT LAKE CITY, UT 84110		UT 84110		ART UNIT PAPER NUMBER	
OIIDI LI	0111,			2825	

DATE MAILED: 07/21/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		lh
	Application No.	Applicant(s)
	10/706,244	IYER ET AL.
Office-Action-Summary	Examiner	Art Unit
	Caridad M. Everhart	2825
The MAILING DATE of this communication apperiod for Reply	pears on the cover sheet with the c	correspondence address
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a repl - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b).	I36(a). In no event, however, may a reply be tin ly within the statutory minimum of thirty (30) day will apply and will expire SiX (6) MONTHS from e, cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).
Status		
1)☐ Responsive to communication(s) filed on 2a)☐ This action is FINAL. 2b)☒ This 3)☐ Since this application is in condition for allowa closed in accordance with the practice under the practice under the practice.	s action is non-final. nce except for formal matters, pro	
Disposition of Claims		
4) Claim(s) 1-50 is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) Claim(s) is/are allowed. 6) Claim(s) 1-50 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/o	wn from consideration.	
Application Papers		
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) accomposed and applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Examine	cepted or b) objected to by the drawing(s) be held in abeyance. Set tion is required if the drawing(s) is objected.	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	ts have been received. ts have been received in Applicati nity documents have been receive u (PCT Rule 17.2(a)).	ion No ed in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892)	4) □ (***********************************	(DTO 442)
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date <u>11-12-2003</u>. 	4)	

Art Unit: 2825

Double Patenting

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970);and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Claims 1-50 are rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1-28 of U.S. Patent No. 6,340,637B1. Although the conflicting claims are not identical, they are not patentably distinct from each other because the claims differ by the line "placing the substrate within a plasma-enhanced deposition chamber". It would have been obvious to one of ordinary skill in the art at the time of the invention to have modified the claims of the invention in order to recite this limitation because the claims are drawn to a plasma process in which a plasma is formed in the deposition chamber, so that a plasma enhanced deposition chamber would have been obvious, and the placing of a substrate in the chamber is a conventional step. With respect to the words "forming" rather than "providing", claim 29 of the application recites "forming". With respect to the words "flowing" rather than "admitting", this variation is obvious to one of ordinary skill in the art because the gaseous components would be expected to flow in the processing which is

Art Unit: 2825

conventional in the art in a CVD or PECVD processing chamber, in which the reactants are flowed into and the by-products are flowed out of the chamber during the process.

The references cited and not relied upon are considered relevant to applicant's dislosure as background references.

Samukawa (US 6,348,158B1) discloses control of the energy distribution in a plasma process of a semiconductor.

Gaughen, et al. (US 2001/0000867A1) discloses control of ionization energies in a CVD process.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Caridad M. Everhart whose telephone number is 571-272-1892. The examiner can normally be reached on Monday through Fridays 7:30-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew S. Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

Art Unit: 2825

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

C. Everhart 7-16-2004 CAPIBAD EVERHALT PRIMARY EXAMINED